

Form PTO-1449 U.S. Department of Commerce Patent and Trademark Office INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	(Rev. 8-88)	Attorney Docket No. 1508.63671	Div. of Ser. No. 08/955
	Applicant Shigeru Okamoto		
	Filing Date 10/29/97	Group 2823	

U.S. PATENT DOCUMENTS

Examiner initial*	Document No.	Date	Name	Class	Subclass	Filing Date
KB	4,990,997	Feb. 5, 1991	Nishida	357	71	Apr. 14, 1989
KB	5,070,036	Dec. 3, 1991	Stevens	437	180	May 18, 1990
KB	5,290,733	Mar. 1, 1994	Hayasaka et al.	437	194	Aug. 6, 1992
KB	5,464,666	Nov. 7, 1995	Fine et al.	427	576	Feb. 6, 1995
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KB	5,552,341	Sep. 3, 1996	Lee	437	192	Dec. 10, 1993
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KB	John A.T. Norman, David A. Roberts et al., ENHANCED DEPOSITION OF COPPER FILMS BY CVD -				
	Advanced Metalization for ULSI Application pp. 57-62				
KB	Susan L. Cohen, Michael Liehr and Srinandan Kasi, Mechanisms of copper chemical vapor depositions, Appl.				
	Phys. Lett. 60 (1), January 6, 1992, pp. 50-52				

Examiner Kurt Eaton	Date Considered 2/6/01
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*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.